Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1	("6653231").PN.	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	OR	OFF	2005/01/10 18:13
L2	39	((430/314,316,319-320,328-329). ccls. and ((oxygen or "O.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash$3 or etch$3))) and (heat$3 or bak$3) same (resist or photoresist)	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	OR	ON	2005/01/10 18:38
L3	83	(((resist or photoresist) and (napthoquinonediazide or naphthoquinonediazide or napthoquinonediazido or naphthoquinonediazido or diazidonapthoquinone or diazidonaphthoquinone)) and (novolac or novolak) and dissolution near3 accelerat$3) not 2	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	OR	ON	2005/01/10 18:49
L5	102	((resist or photoresist) same (polymethylglutarimide or PMGI) same (ash$3 or etch$3 or trim$4 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 or reduc$3 or decreas$3 or slim$3 or less$5 or tight$5)) not 2 not 3	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	OR	ON	2005/01/10 18:54
L6	13	((resist or photoresist) same (polymethylglutarimide or PMGI) same (ash$3 or etch$3 or trim$4 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 or reduc$3 or decreas$3 or slim$3 or less$5 or tight$5) same (bond$3 or adhe$8 or strength$5 or strong$2)) not 2 not 3	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	OR	ON	2005/01/10 19:01
L7	66003	((magnetic adj head or magneto adj resistive or magnetoresistive or magnetophotoresistive or magneto adj photoresistive or giant adj magneto$15 or (GMR same magneto$15)).ti,ab.)	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	OR	ON	2005/01/10 19:11
L8	2549	7 and (resist or photoresist) same (ash$3 or etch$3 or trim$4 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 or reduc$3 or decreas$3 or slim$4 or less$5 or tight$5) not 2 not 3 not 6	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	OR	ON	2005/01/10 19:17

L9	64	7 and ((resist or photoresist) same (ash$3 or etch$3 or trim$4 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 or reduc$3 or decreas$3 or slim$4 or less$5 or tight$5) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))) not 2 not 3 not 6	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	OR	ON	2005/01/10 19:32
L10	221	8 and ((resist or photoresist) same (ash$3 or trim$4 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 or reduc$3 or decreas$3 or slim$4 or less$5 or tight$5) same (heat$3 or bak$3)) not 2 not 3 not 6 not 9	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	OR	ON	2005/01/10 19:35
L11	95	8 and ((resist or photoresist) same (ash$3 or trim$4 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 or reduc$3 or decreas$3 or slim$4 or less$5 or tight$5) same (heat$3 or bak$3)) and ((resist or photoresit) same (mill$3 or ion adj beam or FIB or RIE or ion adj etch$3 or sputter$3)) not 2 not 3 not 6 not 9	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	OR	ON	2005/01/10 19:37
L12	182	8 and ((resist or photoresist) same (ash$3 or trim$4 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 or reduc$3 or decreas$3 or slim$4 or less$5 or tight$5) same (heat$3 or bak$3)) and (((resist or photoresist) same (mill$3 or ion adj beam or FIB or RIE or ion adj etch$3 or sputter$3 or lift$3 adj off or liftoff or remov$3 or etchback or etch$3 adj back))) not 2 not 3 not 6 not 9	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	OR	ON	2005/01/10 19:46
L13	5	8 and ((resist or photoresist) same ("T" adj shap$3 or trapezoid or overh?ng$3 or undercut$4) same (ash$3 or trim$4 or narrow$3 or shrink$3 or shrunk$3 or contract$3 or small$3 or littl$3 or reduc$3 or decreas$3 or slim$4 or less$5 or tight$5) same (heat$3 or bak$3)) and (((resist or photoresist) same (mill$3 or ion adj beam or FIB or RIE or ion adj etch$3 or sputter$3 or lift$3 adj off or liftoff or remov$3 or etchback or etch$3 adj back))) not 2 not 3 not 6 not 9	US-PGPUB; USPAT; EPO; JPO; IBM_TDB	OR	ON	2005/01/10 19:47